



Silver structures in the range of microns

LAB TECHNOLOGY

PHOTOMETALLIZATION - NEW TOUCHSCREENS

OBJECTIVES

- Flexible and cost-saving fabrication of electrically conductive macro- and microstructures on glass- and plastic-substrates.
- Substitution of strategic elements (ITO)

METHOD

- Coating of the substrate with photoactive compound
- Wetting of the substrate with silver complex suspension
- Irradiation with UV-light produces metallic silver films

The structuring can be either done by

- Direct writing with a laser
- Irradiating through a photo mask (contact, proximity or projection)
- Irradiating through a flexible, UV-transparent stamp

RESULTS

- Silver structures up to a thickness of 100 nm on rigid or bendable substrates
- Structure width down to micron range
- ▶ Sheet resistance down to 200 m Ω / \Box
- Alternatively also applicable for copper or gold structures

APPLICATIONS

- Circuitry for display technology and touchscreens
- Contacting in photovoltaics
- ▶ Intelligent packaging via printed electronics

Examples for suitable substrates:

- Glass
- Ceramics
- ▶ **PC** Polycarbonate
- PET Polyethyleneterephthalate
 - PI Polyimide
- PMMA Polymethylmethacrylate
- **PVC** Polyvinylchloride

CONTACT

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